Change of Total Refractive Index in Finite V-shaped Quantum Well*

Lu Zhi'en, Guo Kangxian

Department of Physics, Guangzhou University, Guangzhou 510405

Abstract The change of refractive index in finite V-shaped quantum well is investigated. The first- and third-harmonic generation coefficient is obtained by using Compact-density-matrix approach and iterative method, and the numerical results are presented for GaAs/AlGaAs finite V-shaped quantum well. The results show that the change of total refractive index will be large with decreasing incident intensity.

Keywords Optical refractive index; Finite V-shaped quantum well; Harmonic generation

CLCN O431. 2

Document Code A

0 Introduction

Since the end of 1980s, basic investigations on properties[1~6,14~16] nonlinear optical semiconductor quantum wells, quantum wires, quantum dots, superlattices and macrostructures have attracted much attention in theoretical and applied physics, because of their relevance for studying practical applications and as a probe for the electronic structure of microscopic media. The research results have shown that decrease in dimensionality of the system for semiconductor can dramatically a enhancement nonlinearities[7]. With the quantum confinement of a carrier in a semiconductor, the discrete energy levels are formed. These energy level tailored by modifying the shape of a well using different compositions profiles and external potentials. The quantum size effect drastically changes the electronic and optical properties of the well material.

Nonlinear refractive index change, one of nonlinear optical properties, has been calculated in a single quantum well, poly quantum wells, quantum dots in the past. In 1987, Tohya Hiroshima^[8] presented the nonlinear refractive index change in GaAs/Al_xGa_{1-x} As quantum well in the electric field. The field effect on the refractive index in GaAs/Al_xGa_{1-x} As quantum well by Yasuo Kan^[9]. In 1991, Kelin J. Kuhn^[10] presented free carrier induced change of the refractive index in GaAs/Al_xGa_{1-x} As quantum

Tel;020-86237563 Email;zhienlu@sohu.com Received date;2005-03-08 well. They all obtained very large refractive index change. Modifying the shape of a quantum well can change the system wavefunction and the energy level, which both would drastically change optical properties. In this paper, it only concentrates on V-shaped quantum well and the study of nonlinear refractive index change.

1 Theory

Here, it is considered that a finite V-shaped quantum well as following

$$V(z) = \begin{cases} 0 & (z < -L) \\ -V_0 + \frac{V_0}{L} |z| & ((\frac{V_0 + E}{V_0})L \leq z \leq L) \\ 0 & (Z > L) \end{cases}$$

$$(1)$$

where V(z) is the confining potential, z represents the growth of the well, z axis is perpendicular to the well layer, L is the width of VQW, V_0 is a parameter in describing confining potential.

It was supposed an electron confined in such VQW. In the effective mass approximation, the Hamiltonian of the electron in VQW is

$$H = -\frac{\hbar^2}{2m_*^2} \nabla + V(z) \tag{2}$$

where m_e^* is the effective mass of the electron, \hbar is Planck' constant. So the Schrödinger equation can be written as following

$$\left[-\frac{\hbar^2}{2m_e^*}\nabla + V(z)\right]\Psi(z) = E\Psi(z)$$
 (3)

The solvation of Eq. (3) and its energy level are given by

$$\Psi_{1}(\xi) = C_{1} \sqrt{|\xi|} \{J_{1/3}(2|\xi|^{3/2}/3) + J_{-1/3}(2|\xi|^{3/2}/3)\} \quad (0 \leqslant z \leqslant (\frac{V_{0} + E}{V_{0}})L)$$

$$\Psi_{2}(\xi) = C_{2} \sqrt{|\xi|} \{I_{1/3}(2|\xi|^{3/2}/3) + K_{1/3}(2|\xi|^{3/2}/3)\} \quad ((\frac{V_{0} + E}{V_{0}})L \leqslant z \leqslant L)$$

$$\Psi_{3}(z) = De^{-\beta z} \quad (L \leqslant z)$$

$$\Psi_{4}(z) = De^{\beta z} \quad (z \geqslant -L)$$
(4)

^{*}Supported by the National Natural Science Foundation of China (No. 60478010), Science and Technology Committee of Guangdong Province (Nos. 2003c103021, 2004B10301014 and 04105406) and Science and Technology Bureau of Guangzhou (Nos. 200J1-C0031 and 2004J1-C0226)

where $\xi = \sqrt[3]{\frac{2m_{\rm e}^*L^2}{\hbar^2V_0^2}}$ ($E + V_0 - \frac{V_0}{L}z$) and J, I, K represent BesselJ function, BesselI function and BesselK function respectively, $\beta = \sqrt{\frac{-2m_{\rm e}^*E}{\hbar}}$, C_1 , C_2 and D is normalization constant

$$E_n = -V_0 + V_0 \left\{ \frac{3\pi \hbar}{4L \sqrt{2m_e^* V_0}} (n + \frac{1}{2}) \right\}^{2/3}$$
 (5)

where n means the number of the energy level of the VQW.

In the below, it will derive the expression of linear and nonlinear Optical index change in VQW. Let us suppose VQW with an optical field with frequency ω which is incident with a polarization vector normal to VQW. The incident electronic field is defined as

$$E(t) = \widetilde{E}e^{i\omega t} + \widetilde{E}e^{-i\omega t}$$
 (6)

Let the symbol ρ denote the one-electron density matrix operator for this regime. The evolution of one-electron density matrix obeys the following time-dependent Schrödinger equation

$$\frac{\partial \rho_{ij}}{\partial t} = (i \hbar)^{-1} [H_0 - qzE(t), \rho]_{ij} -$$

$$\Gamma_{ij} \left(\rho - \rho^{(0)} \right)_{ij} \tag{7}$$

where, $\rho^{(0)}$ is the unperturbed density matrix, Γ is the relaxation time. For simplicity, we assume that all of the off-diagonal elements of Γ are same and $\Gamma_{ij} = 1/\Gamma_1$, and all of the diagonal elements of Γ are adopted the other same value too, $\Gamma_{ij} = 1/\Gamma_2$. Equation is usually solved using iterative method^[11]

$$\rho(t) = \sum_{n} \rho^{(n)}(t) \tag{8}$$

With

$$\frac{\partial \rho_{ij}^{(n+1)}}{\partial t} = \frac{1}{\hbar} \{ [H_0, \rho^{(n+1)}]_{ij} - i \hbar \Gamma_{ij} \rho_{ij}^{(n+1)} \} - \frac{1}{i \hbar} [er, \rho^{(n)}]_{ij} E(t)$$
(9)

In this text, it only concentrate on electronic transition between the ground state and the first excited state. The electronic polarization P(t) of VQW can be expanded as equation(9), it is be limit to considering the first three orders

$$P(t) = \varepsilon_0 \chi_{\omega}^{(1)} \widetilde{E} e^{-i\omega t} + \varepsilon_0 \chi_{2\omega}^{(2)} \widetilde{E} e^{-2i\omega t} + \varepsilon_0 \chi_{3\omega}^{(3)} \widetilde{E} e^{-3i\omega t} + c. c.$$
(10)

where it's limited to considering the first three orders, ε_0 is the vacuum permittivity, $\chi^{(1)}$, $\chi^{(2)}_{2\omega}$, $\chi^{(3)}_{3\omega}$ are the linear, second-harmonic generation and third-harmonic generation coefficients, respectively. As V-shaped potential is symmetrical, $\chi^{(2)}_{2\omega}$ will be zero. So it only need calculate linear and third-harmonic generation coefficients $\chi^{(1)}$,

 $\chi_{3\omega}^{(3)}$. By using density matrix method, it can find the expression of linear and third-harmonic generation coefficient $\chi^{(1)}$, $\chi_{3\omega}^{(3)}$. So it lays emphasis on the calculations of the change of the first and third order optical refractive index change. They obey the following equation [12]

$$\frac{\Delta n(\omega)}{n_{r}} = \operatorname{Re}(\frac{\chi(\omega)}{2n_{r}}) \tag{11}$$

Finally, the expressions of optical refractive index change was obtained.

$$\frac{\Delta n^{(1)}(\omega)}{n_{\rm r}} = \frac{\rho_{\rm s} I}{2\varepsilon_0 n_{\rm r}} |M_{10}|^2 \left[\frac{\hbar \omega_{10} - \hbar \omega}{(\hbar \omega_{10} - \hbar \omega)^2 + (\hbar \Gamma_{01})^2} \right]$$
(12)

$$\frac{\Delta n^{(3)}(\omega,I)}{n_{\rm r}} = -\frac{uc}{4n_{\rm r}^3\epsilon_0} |M_{10}|^2 \{\rho_{\rm s}I/[(\hbar\omega_{10} - \hbar\omega)^2 + (\hbar \Gamma_{01})^2]^2\} [4 (\hbar \omega_{10} - \hbar \omega) |M_{10}|^2 - \frac{(M_{11} - M_{00})^2}{(\hbar\omega_{10})^2 + (\hbar \Gamma_{01})^2} \{(\hbar \omega_{10} - \hbar \omega) [\hbar \omega_{10} (\hbar \omega_{10} - \hbar \omega) - (\hbar \Gamma_{10})^2] - (\hbar \Gamma_{01})^2 (2 \hbar \omega_{10} - \hbar \omega)] (13)$$
where $\omega_{10} = \frac{E_1 - E_0}{\hbar}$ is Bohr frequency, $M_{ij} = \langle \Psi_j | qz | \Psi_i \rangle$ is the dipole matrix $(i,j=0,1)$, $\rho_{\rm s}$ is the electron density in the VQW. I is the optical power unit area, $n_{\rm r}$ is the refractive index without nonlinear optical effect, u is the permeability of the system and c is the light speed in vacuum.

2 Results and discussions

The parameters used in numerical work are adopted as^[13]: $m_e^* = 0.067 m_0$, $n_r = 3.2$, $\epsilon_0 = 8.85 \times 10^{12} \, \text{F} \cdot \text{m}^{-1}$, $V_0 = 0.1 \, \text{eV}$, $\rho_s = 5 \times 10^{22} \, \text{m}^3$.

In Fig. 1, it plots the values of the linear, third-order and total refractive index change versus the phonton energy $h\nu$ for incident intensity I=1 mW/cm³. From this figure it was see that the third-order refractive index change $\Delta n^{(3)}$ can not be ignored, comparing with the linear refractive index change $\Delta n^{(1)}$. On the other hand, the value of $\Delta n^{(3)}$ has a opposite sign to the value of $\Delta n^{(1)}$, so it creates the value of Δn_{total} decreasing. Therefore the third-order

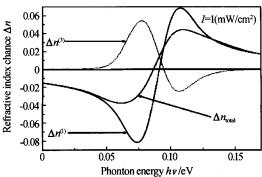


Fig. 1 The linear, third-order and total refractive index change in finite V-shaped quantum well versus the phonton energy $h\nu$ for incident intensity I=1 mW/cm³

nonlinear refractive index change has a marked influence on the change of refractive index.

In Fig. 2, the linear, the third-order and total refractive index change are plotted as functions of phonton energy for the other big incident intensity $I=3~\mathrm{mW/cm^3}$. From Fig. 3, it was seen that linear refractive index change is the same as above in Fig. 1, after increasing incident intensity. It means that linear index change is not related to incident intensity, which it's also can be obtained in equation (12). However, the third-order refractive index change makes a large change and it even surpasses the peak value of linear refractive index change when the incident optical intensity exceeds certain value.

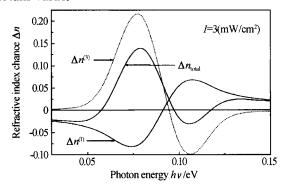


Fig. 2 The linear, third-order and total refractive index change in finite V-shaped quantum well versus the phonton energy h_{ν} for incident intensity I=3 mW/cm³

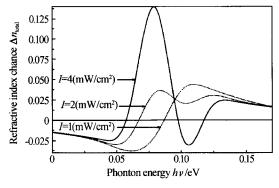


Fig. 3 The total refractive index change in finite V-shaped quantum well versus the phonton energy $h\nu$ for incident intensity $I=1~{\rm mW/cm^3}$, $2~{\rm mW/cm^3}$, $4~{\rm mW/cm^3}$

In Fig. 3, it's plotted the value of total refractive index change versus the phonton energy $h\nu$ for incident intensity I=1 mW/cm³, 2 mW/cm³, 4 mW/cm³, respectively. When increasing incident intensity, the total refractive index change will be smaller concomitantly. So if we want to give a larger change of refractive index change in practice, a relatively weaker incident optical intensity should be adopted. It was also seen that the total refractive index change become large when the incident optical is equal to the value of 4 mW/cm³. It also

means adopting the value 4 mW/cm³ have exceed the saturated value.

3 Conclusion

It's present a simple and straightforward study of linear, nonlinear and total refractive index change in finite V-shaped quantum well by density matrix method. The main results show that the incident optical intensity effects on the nonlinear refractive index change, however the linear refractive index change is not related to the incident optical intensity. Furthermore the total refractive index change will become larger with the incident optical increasing intensity. Theoretical study may provide a power proof on experiment applies as regards practical applications on electro-optical devices.

References

- 1 Chemla D S. Nonlinear optics in quantum-confined structures. *Physics Today*, 1993, **46**(6):46~52
- 2 Zhang Li, Xie HongJing, Chen Chuanyu. Second2 order nonlinear optical susceptibility of a semi2 parabolic quantum well with an applied electronic field. Acta Photonica Sinca, 2003, 32(4):438~440
- Tan Peng, Guo Kangxian, Li Bin, et al. Calculation of linear and nonlinear intersubband optical absorption in the Po schl2 teller well. Acta Photonica Sinca, 2003, 32 (7):815~818
- 4 Zhou Jun, Jia Zhen Hong. Nonlinear optical refractive and absorption properties of a novel amorphous molecular material. Acta Photonica Sinica, 2003, 32 (11): 1332 ~ 1335
- 5 Hu Zhenhua, Chen Jun, Miao Qinyuan, et al. Theoretical studies of nonlinear properties for V-level atoms in vacuum by using time translational matrix method. Acta Phontonica Sinica, 2002, 31(5):520~526
- 6 Yuh P F, Wang K L. Optical transition in a step quanatum well. JAppl Phys, 1989, 65(4):4377~4381
- 7 Schmitt-Rink S, Chemla D S, Miller D A B. Linear and nonlinear optical properties of semiconductor quantum wells. Adv Phys, 1989, 38(12):89~188
- 8 Hiroshima Tohya. Electric field induced refractive index changes in GaAs/Al_xGa_{1-x}As quantum wells. Appl Phys Lett, 1987, 50(15):968~970
- 9 Yasuo K, Hideo N, Masamichi Y, et al. Field effects on the refractive index and absorption coefficient in AlGaAs quantum well structures and their feasibility for electrooptic device application. IEEE Journal of Quantum Electronics, 1987, QE-23(27):2167~2180
- 10 Kuhn Kelin J, Lyengaar Gita U, Yee Sinclair. Free carrier induced change of the refractive index in GaAs/Al_xGa_{1-x}As quantum well, J Appl Phys, 1991, 71(9): 5010~5017
- 11 Rosencher E, Bois Ph. Model system for nonlinearities: asymmetric quantum wells. Phys Rev B, 1991, 44(15):

- $11315 \sim 11327$
- 12 Chuang S L, Ahn D. Optical transitions in a parabolic quantum well with an applied electric field-analytical solution. J Appl Phys., 1988, 66(9):8822~8826
- 13 Guo Kangxian, Chen Chuanyu. Polaron effects on optical rectification in electric-field-biased parabolic quantum wells. J Phys Condens Matter, 1995, 7(32):6583~6588
- 14 Li Wenbing, Zhao Guozhong, Wang Fuhe, et al. Intersubband transition optical absorption of
- semiconductor supperlattice. Acta Photonica Sinica, 2006, 35(1):61~64
- 15 Chen Ming, Xu Mai, Li Chunfei, et al. Optical switch and bistaility based on nonlinear one — dimensional photonic crystals. Acta Photonica Sinica, 2005, 34(1): 98~101
- 16 Liu Chihong. Third order nonlinear optical susceptibility in a cylindrical quantum dot. Acta Photonica Sinica, 2005, 34(11):1740~1744

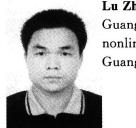
有限深V型势阱中总折射率的改变

报

陆志恩 郭康贤 (广州大学物理系,广州 510405) 收稿日期:2005-03-08

摘 要 研究了有限深 V 型势阱折射率改变,并且利用量子力学中的密度矩阵算符理论和迭代法导出了一次,三次谐波极化率系数.最后,以 GaAs 有限深 V 型势阱为例作了数值计算.数值结果表明,减少入射光强度,或增加电子浓度使总折射率改变变大.

关键词 有限 V 型势阱; 光折射率; 谐波产生



Lu Zhi'en was born in Guangzhou, China, on November 25, 1979. He graduated from Guangzhou University with the bachelor degree in 2003. He is now majoring in optical nonlinearities in low-dimensional semiconductor structures for his master degree in Guangzhou University.